

LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

ABSTRACT

The present invention relates to a lithographic projection apparatus comprising a housing, which comprises therein a first exposure system that has at least one movable part, e.g. a movable first substrate holder, or a movable second substrate holder in a twin stage apparatus. The system is further provided with position disturbance correction system for correcting a position of the first substrate holder with respect to the patterned projection beam due to the influence of gas pressure differences or gas movements, caused by movements of the movable part.

The invention also generally relates to a device manufacturing method comprising providing a lithographic projection apparatus according to the invention with a first substrate, and exposing said first substrate, wherein during said exposing of the first substrate a position thereof is corrected by means of position disturbance correction system.